

Nanotech 2003, Feb. 23-27, San Francisco

Workshop on Compact Modeling

Tu25.03, Proc. vol.2, pp.246-249

## **A BASIC PROPERTY OF MOS TRANSISTORS AND ITS CIRCUIT IMPLICATIONS**

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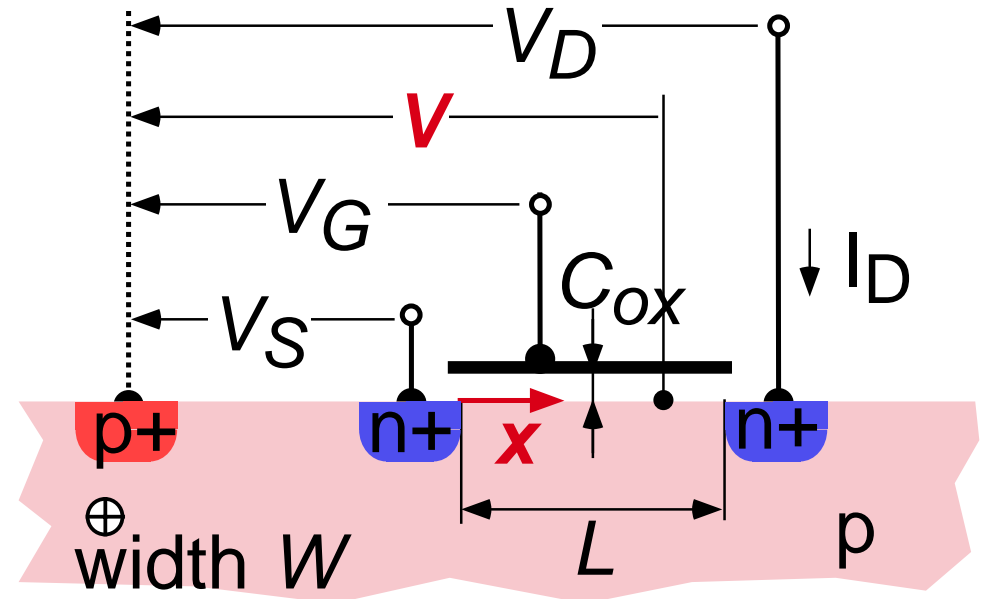
## INTRODUCTION

- Goals of transistor modeling:
  - simulation by quantitative calculation on computer
  - highlighting properties to facilitate
    - understanding circuits
    - synthesis of robust circuits
- Best models: combine both goals by hierarchical structure  
example: EKV model.
- EKV approach will be used to explicit a basic property.

## DEFINITIONS

for EKV model

- Substrate referred-voltages  
 $V_S, V_D, V_G$



- Local "channel voltage"  $V$   
splitting of quasi-Fermi levels due non-0  $V_S$  and/or  $V_D$

$$V = V_S \text{ at source}$$

$$V = V_D \text{ at drain}$$

n-channel: holes at equilibrium

thus  $V = \text{electron quasi-Fermi level} + \text{constant}$ .

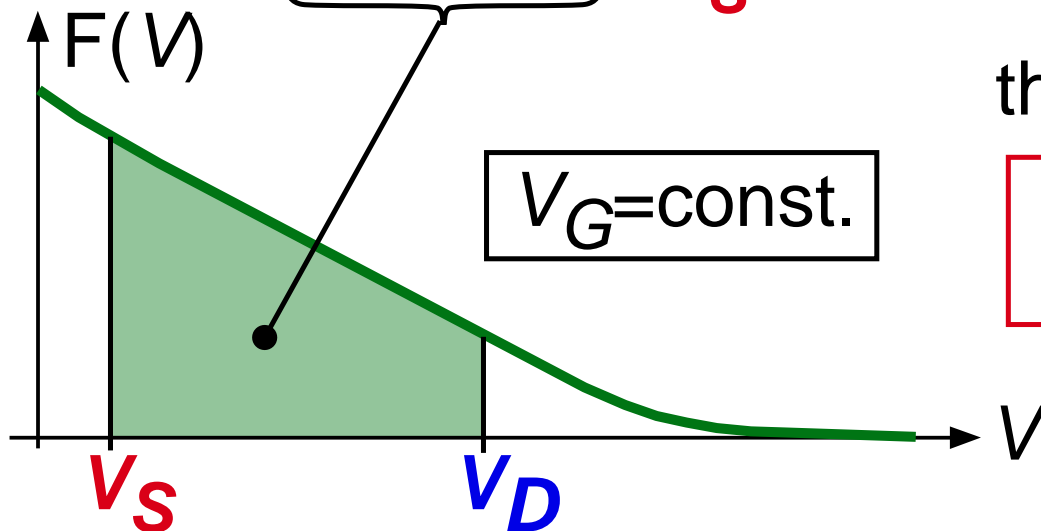
# BASIC PROPERTY (1)

- For a long and wide channel:

$$I_D = \mu W(-Q_i) \frac{dV}{dx} \stackrel{=}{=} \frac{F(V, V_G)dV}{G(x, V_G)dx}$$

- Condition: **separable** in  $V$  and  $x$

$$\text{then: } I_D \int_0^L G dx = \int_{V_S}^{V_D} F dV \equiv \int_{V_S}^{\infty} F dV - \int_{V_D}^{\infty} F dV$$



thus:

$$I_D = I(V_S, V_G) - I(V_D, V_G)$$

## BASIC PROPERTY (2)

$$I_D = I(V_S, V_G) - I(V_D, V_G)$$

- The drain current is the **superposition** of **independent** and **symmetrical** effects of source and drain voltages.
- Definitions:
  - **Forward** current  $I_F = I(V_S, V_G)$ , independent of  $V_D$
  - **Reverse** current  $I_R = I(V_D, V_G)$ , independent of  $V_S$

$$\text{then } I_D = I_F - I_R$$



## DOMAIN OF VALIDITY (2)

- Condition:

$$\mu W(-Q_j) = \frac{F(V, V_G)}{G(x, V_G)}$$

- $W$  is independent of  $V$ ; thus:
  - part of  $G$ , may depend on  $x$ :  $\Rightarrow$  any shape of channel.
- Mobility  $\mu$  depends on vertical field thus on  $\Psi_S$ , thus
  - included in  $F$ , provided velocity  $v \ll v_{sat}$   
(otherwise depends on  $I_D$  itself)
- Furthermore, the effective value of  $L$  along which  $G(x, V_G)$  is integrated must be independent of  $I_D$ ,  $V_S$  and  $V_D$ .

## EFFECT OF NARROW CHANNEL

- Increased importance of side effects.
- Equivalent to parallel connection of several transistors with different characteristics.
  - if each transistor  $i$  fulfils

$$I_{Di} = I_i(V_S, V_G) - I_i(V_D, V_G)$$

- then the sum  $I_D$  of  $I_{Di}$  fulfils it as well.
- The property is not degraded.

## DOMAIN OF VALIDITY (SUMMARY)

The basic property is available

- For **long** and **homogeneous** channel
- Independently of channel shape
- Even if the channel is very narrow
- Even for large gate voltages reducing the mobility.

## CAUSES OF DEGRADATION (1)

- Non homogeneous channel:  $Q_i$  direct function of  $x$ .

$$Q_i = -C_{ox}(V_G - V_{FB} - \Psi_s) + \sqrt{2q N_b \epsilon_{si} \Psi_s}$$

There may be variations with position  $x$  in the channel of:

- substrate doping  $N_b$ , which can be
  - intentional (e.g.: LDD)
  - artifact of process (gradient or piling-up )  
(always present at very ends of channel)
- flat-band voltage  $V_{FB}$ , caused by
  - variation of  $N_b$
  - variation of charge in oxide
- effective  $C_{ox}$ , always present at very ends of channel.

## SPECIAL CASE OF WEAK INVERSION

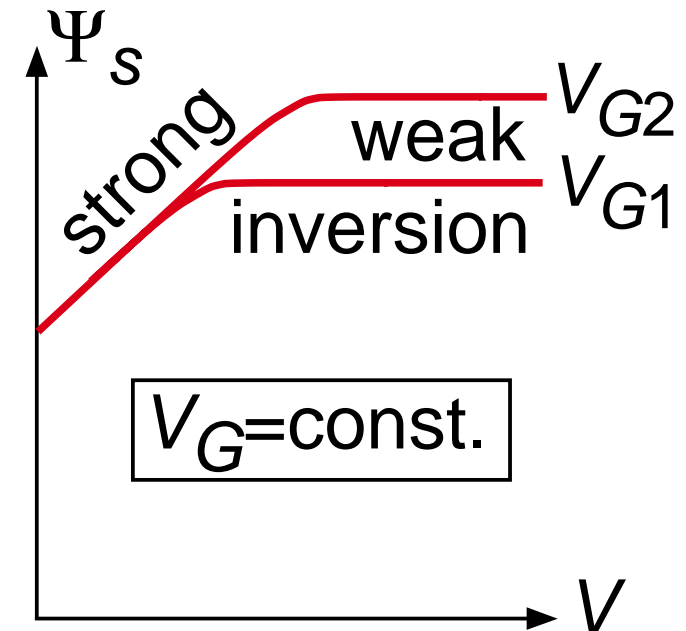
- Weak inversion characterized by  $Q_i \ll Q_b$ , therefore:
  - $Q_i$  has negligible effect on potential and field

- Can be expressed as  $-Q_i = G_q(\Psi_s)e^{-V/U_T}$

- with  $\Psi_s$  independent of  $V$ , thus:

- $G_q$  can be any function of  $x$  and is included in  $G$ , therefore:

- The property is valid even if the channel is not homogeneous.



- Mobility  $\mu$  independent of  $V$ , thus part of  $G$ ,  
 $F$  is reduced to  $F = e^{-V/U_T}$ : independent of  $V_G$ .

## CAUSES OF DEGRADATION (2)

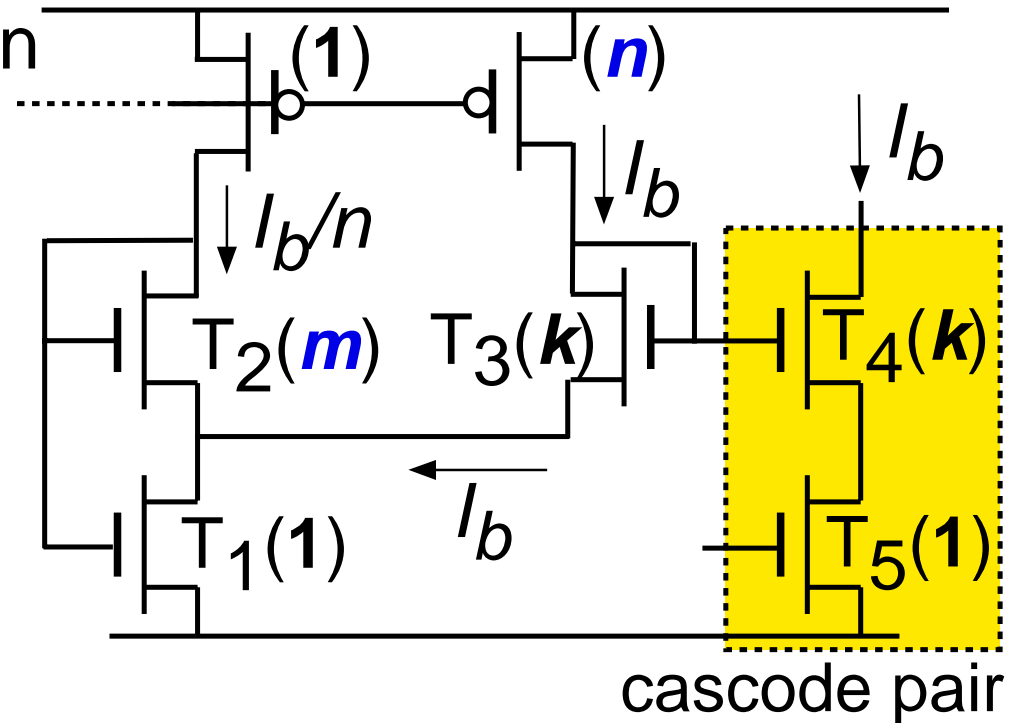
- Channel long  $\Rightarrow$  non-long  $\Rightarrow$  short
  - property progressively degraded by...
  - several independent mechanisms:
    - a.** Voltage effects:
      - channel length modulation
        - $I_F$  or  $I_R$  becomes function of both  $V_D$  and  $V_S$
        - effect proportional to  $1/L$
      - barrier lowering and 2-D effects: further degradation.
    - b.** Current effects:
      - if  $I_D$  is increased by reducing  $L$ , then
        - $\Rightarrow$  carrier velocity increases towards saturation
        - $\Rightarrow$  mobility reduced, thus function of  $I_D$
    - c.** Non-homogeneous channel (except in weak inversion):
      - importance of end-effects proportional to  $1/L$ .

# CIRCUIT EXAMPLE: LOW-VOLTAGE CASCODE

- Goal:  $V_{D5}$  min. for saturation

- Means: control  $\frac{I_{R5}}{I_{F5}} \ll 1$ :

- $m$  and  $n \gg 1$ , hence:
- $I_{D5} \cong I_{D1}$  with  $V_{D5} = V_{D1}$
- thus  $I_{R5}/I_{F5} \cong I_{R1}/I_{F1}$



$$\left. \begin{array}{l} \bullet I_{F2} = I_b/n = m I_{R1} \\ \bullet I_{F1} \cong I_b \end{array} \right\} \Rightarrow \frac{I_{F1}}{I_{R1}} \cong \boxed{mn} \cong \frac{I_{F5}}{I_{R5}}$$

- Large enough to ensure saturation
- Independent of  $I_b$ .

## CONCEPT OF PSEUDO-RESISTOR

- We have shown that: 
$$I_D = \frac{1}{\int_0^L G dx} \left[ \int_{V_S}^{\infty} F dV - \int_{V_D}^{\infty} F dV \right]$$

- Definitions:
  - pseudo-voltage: 
$$V^* = -K_0 \int_V^{\infty} F(V, V_G) dV$$

- pseudo-resistor: 
$$R^* = K_0 \int_0^L G(x, V_G) dx$$

(where  $K_0$ : any positive constant)

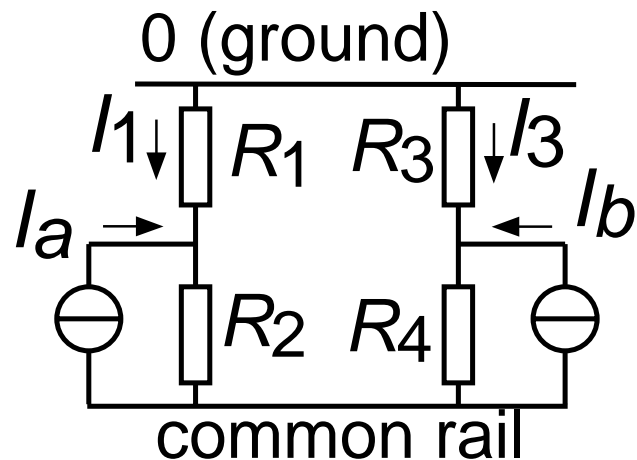
- Results in pseudo Ohm's Law: 
$$I_D = (V_D^* - V_S^*)/R^*$$

## LINEAR CURRENT-MODE CIRCUITS

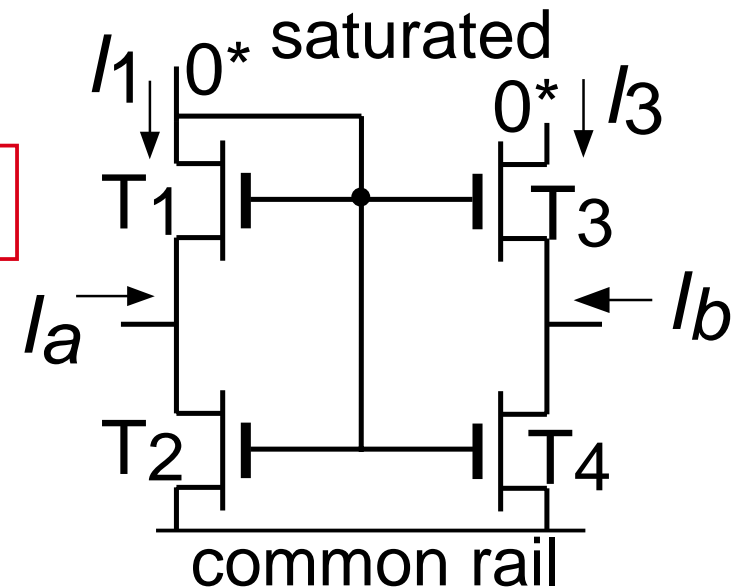
- Implications of pseudo Ohm's law  $I_D = (V_D^* - V_S^*)/R^*$ 
  - Any network interconnecting transistors with same  $F(V, V_G)$  and **same  $V_G$**  is **linear with respect to currents**.
  - Any circuit of linear resistors can be implemented by **transistors only**, provided only currents are considered.
  - A resistor connected to ground ( $V=0$ ) in the resistive prototype corresponds to a **saturated** transistor that provides a **pseudo-ground** ( $V^*=0$ ).
- In weak inversion:
  - $F$  indep. of  $V_G$ , but  $V_G$  included in function  $G$ , hence:
  - **Different  $V_G$  possible** for each transistor
  - Each  **$R^*$  can be separately adjusted** by its  $V_G$ .

# APPLICATION OF PSEUDO-RESISTORS

(example)



$$R_i \sim L_i / W_i$$



$$(R_3 + R_4)I_3 + R_4I_b = (R_1 + R_2)I_1 + R_2I_a$$

thus: 
$$I_3 = k_1 I_1 + k_a I_a - k_b I_b$$

- Output  $I_3$  is the **weighted sum** of  $I_1$ ,  $I_a$  and  $-I_b$ .
- $I_a$  is **low-voltage** input ( $T_2$  not saturated)
- For  $R_4=0$  ( $T_4$  in s/c) and  $T_1=T_2=T_3 \Rightarrow k_1 = 2$ 
  - for  $N$  unit trans. in series at input  $\Rightarrow k_1 = N$
  - for  $M$  units in parallel at output  $\Rightarrow k_1 = \mathbf{M.N}$

## FURTHER APPLICATIONS OF PSEUDO-RESISTORS

- Linear attenuators (electrical control in weak inversion)
  - R-2R network for D/A conversion.
- Spatial information processing:
  - $n^{\text{th}}$  order moment computation
  - diffusion networks (isotropic or not)
  - 2-D emulation of physical media
  - path finding.
- In weak inversion: exploitation of current distribution in voltage- (or current-) dependent linear networks:
  - local normalisation in vision processing
  - generation of nonlinear functions
  - ...

## CONCLUSION

- Basic MOS property for long and homogeneous channels:

$$I_D = I(V_S, V_G) - I(V_D, V_G) = I_F - I_R$$

- superposition of independent and symmetrical effects of S and D voltages.
- forward and reverse components.
- Property progressively degraded when channel shortened.
- Underlies the concept of pseudoresistor:
  - linear current mode circuits
  - transistor implementation of arrays of resistors.
  - simpler analysis of transistor circuits.